

C1
1. (thrice amended) A method for reducing particle contamination inside a plastic container, comprising coating selected portions of the container with a coating that consists essentially of titanium dioxide so as to attract atmospheric water molecules to produce a hydrophilic surface on the container for facilitating cleaning the container.

C2
10. (thrice amended) An apparatus for reducing particle contamination of an article, comprising a plastic container adapted for holding the article, and a coating on selected portions of said container, said coating consisting essentially of titanium dioxide so as to attract atmospheric water molecules to produce a hydrophilic surface on the container for facilitating cleaning the container.

C3
15. (thrice amended) A method for storing semiconductor wafers, comprising providing a plastic container, providing a coating on said container that consists essentially of titanium dioxide such that the titanium dioxide attracts atmospheric water vapor to produce a hydrophilic surface on the container, and using said container to hold the semiconductor wafers.

C4
23. (once Amended) The apparatus of claim 10 ~~22~~, wherein said coating comprises a gel.

C5
25. (once Amended) The method of claim 15 ~~24~~, further comprising providing said coating in the form of a gel.